

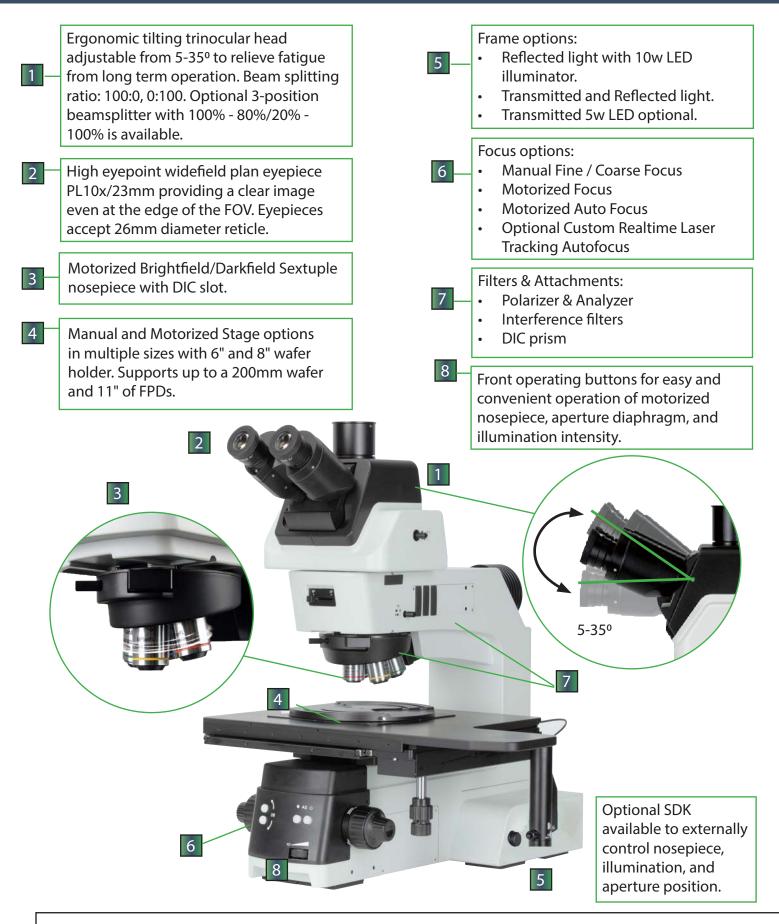
## Advanced Semiconductor Microscopes M68 and M50-12

Fein Optic M68 Brightfield / Darkfield / Polarization / DIC 6" & 8" Wafer

Fein Optic M50-12 Brightfield / Darkfield / Polarization / DIC 12" Wafer

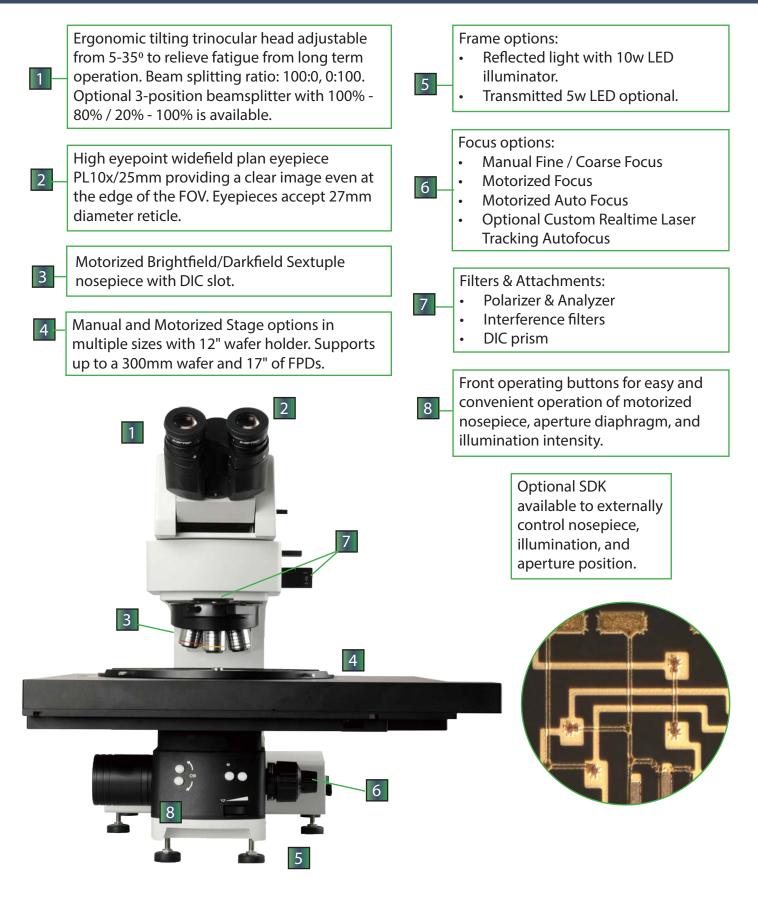


## M68 Advanced Semiconductor Microscope Features





## M50-12 Advanced Semiconductor Microscope Features





#### LWD Brightfield / Darkfield / DIC Plan Achromat Objective Lenses

- LWD Plan Achromat BD DIC 5x, NA 0.15; WD 9.0mm
- LWD Plan Achromat BD DIC 10x, NA 0.3; WD 9.0mm
- LWD Plan Achromat BD DIC 20x, NA 0.45; WD 3.4mm
- LWD Plan Achromat BD DIC 50x, NA 0.55; WD 7.5mm
- LWD Plan Achromat BD DIC 100x, NA 0.80; WD 2.1mm



#### Brightfield / Darkfield Plan Semi Apochromat Objective Lenses

- BD Semi Apochromat 5x, NA 0.15; WD 13.5mm
- BD Semi Apochromat 10x, NA 0.30; WD 9.0mm
- BD Semi Apochromat 20x, NA 0.50; WD 2.5mm
- BD Semi Apochromat 50x, NA 0.80; WD 1.0mm
- BD Semi Apochromat 100x, NA 0.90; WD 1.0mm

#### LWD Brightfield / Darkfield Plan Semi Apochromat Objective Lenses

- LWD BD Semi Apochromat 20x, NA 0.40; WD 8.5mm
- LWD BD Semi Apochromat 50x, NA 0.55, WD 7.5m
- LWD BD Semi Apochromat 50x, NA 0.55; WD 10.6mm
- LWD BD Semi Apochromat 100x, NA 0.80; WD 2.1mm
- LWD BD Semi Apochromat 100x, NA 0.80; WD 3.5mm



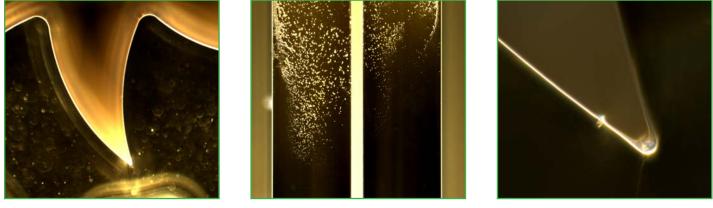


## Advanced Semiconductor Microscope Performance

Fein Optic Advanced Semiconductor Microscope systems are tailored for demanding analysis of Semiconductors and MEMS. Providing multiple contrasting techniques, high optical performance and crisp images, these instruments generate reliable and reproducible results.



The above images of a Silicon wafer with patterned Si02 have a thickness of 1µm and were captured with a 5x objective lens using DIC. The first image notates residual PR (photoresist). The second and third images detail the edge of the wafer illustrating a crisp, detail rich result.



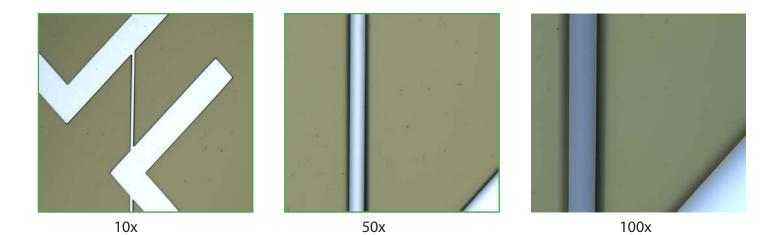
10x

20x

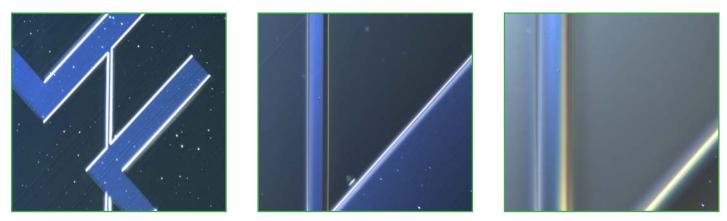
100x

The above MEMS images with Pyrex Gold Chrome and SU-8 were captured using Darkfield at varying magnifications. Details provided in these images allow for the inspections of defects, contaminants, and mechanical stresses.





The above images of a Silicon wafer with thin negative photoresist were captured using Brightfield at varying magnifications. Here the observer is measuring CD, the Critical Dimension of the small line widths to assure quality and integrity during the manufacturing process.



10x

50x

100x

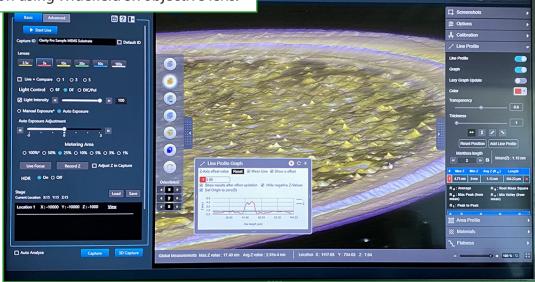
This set of images are identical to the previous set of images with the only variance being the contrast method. Here the images were captured using DIC at varying magnifications. With DIC details become visible that were not present in the images captured using Brightfield.



# Advanced Semiconductor Microscope Optional Accessories

#### **MWZ** Profiler

Widefield Extended Resolution Automatic Surface Profiler. Nanometer level resolution using Widefield 5x objective lens.



P





# Advanced Semiconductor Microscope Optional Accessories



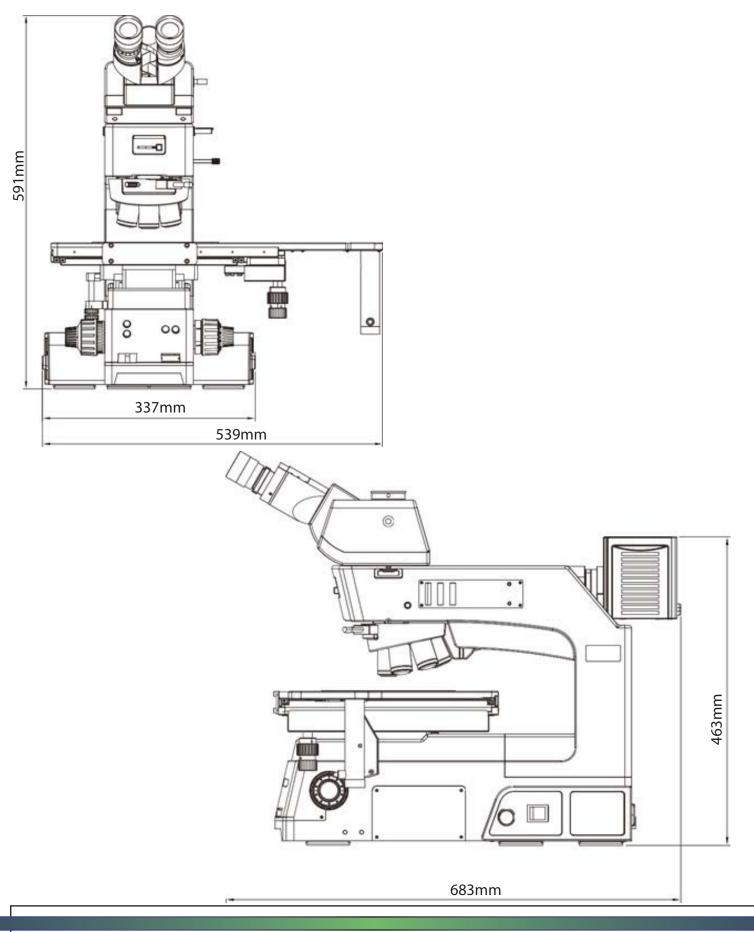


# Advanced Semiconductor Microscope Specifications

Model	M68	M50-12
Optical System	Infinity Color Corrected Optical System	
Modalities	Brightfield, Darkfield, Polarization, DIC	Brightfield, Darkfield, Polarization, DIC
Viewing Head	Ergo tilting trinocular head, upright and erect image, adjustable from 5-35°; beam splitter 100:0 or 0:100. Interpupillary distance 50-76mm.	Ergo tilting trinocular super widefield head, upright and erect image, adjustable from 5-35°; beam splitter 100:0 or 20:80. Interpupillary distance 50-76mm.
Eyepieces	High eyepoint widefield plan eyepiece PL10x/23mm. Eyepieces accept 26mm diameter reticle.	High eyepoint widefield plan eyepiece PL10x/25mm. Eyepieces accept 27mm diameter reticle.
Objective Lenses	Infinity Corrected LWD Brightfield Plan Achromat Objectives 5x, 10x, 20x, 50x, 100x	
	Infinity Corrected High Resolution Brightfield Semi Apo Objectives 5x, 10x, 20x, 50x, 100x	
	Infinity Corrected LWD BD Plan Achromat Objectives 5x, 10x, 20x, 50x, 100x	
	Infinity Corrected BD Semi Apochromat Objectives 5x, 10x, 20x, 50x, 100x	
	Infinity Corrected LWD BD Plan Semi Apochromat Objectives 20x, 50x (WD 7.5mm), 50x (WD 10.6mm), 100x (WD 2.1mm), 100x (WD 3.5mm)	
Nosepiece	Motorized Brightfield / Darkfield Sextuple nosepiece with DIC slot	
Focus Adjustment	Options for Manual fine/coarse focus; Motorized Focus; Motorized Auto Focus. Optional real-time laser tracking autofocus is available. Low position coaxial focus mechanism, coarse range: 35mm, fine precision: 0.001mm. Upper limit and tension adjustment. Built-in 100~240V wide voltage system.	
Frame	Reflected light frame or Transmitted Reflected light frame	
Stage	Manual 158mm x 158mm Manual 210mm x 210mm Motorized 154mm x 154mm Motorized 255mm x 215mm 6" and 8" wafer holder	Manual 305mm x 305mm Motorized 302mm x 302mm 12" wafer holder
Flat Panel Displays (FPDs) Support	Supports 11" of FPDs	Supports 17" of FPDs
Wafer Support	Supports up to a 200mm Wafer	Supports up to a 300mm Wafer
Illumination	10W LED Brightfield/Darkfield reflected illuminator, electronic variable aperture and field diaphragm, center adjustable; switch for changing between BF/DF; slots for filters and polarizing kit.	
Filters & Attachments	IFF50 Yellow filter for photoresist inspection applications. Polarizing kit, Interference filers, DIC prism	
C-Mount Adapter	0.5x / 0.65x / 1x	

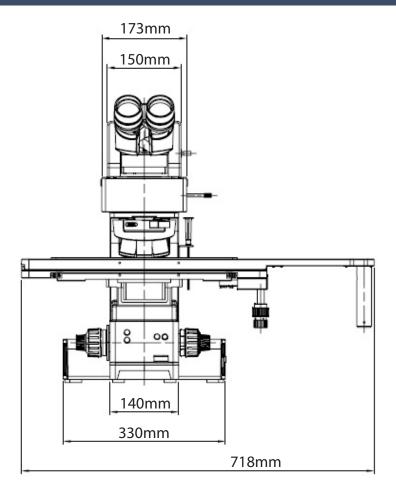


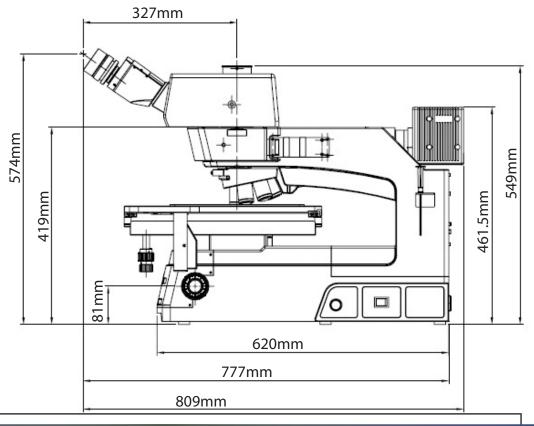
# Fein Optic M68 Advanced Semicondcutor Microscope Dimensions





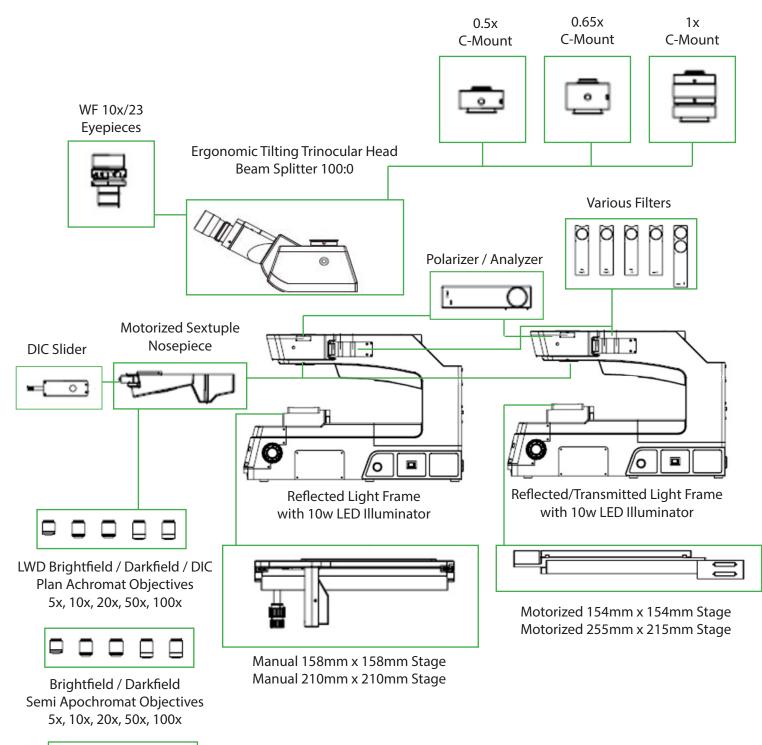
# Fein Optic M50-12 Advanced Semicondcutor Microscope Dimensions







### Fein Optic M68 Advanced Semicondcutor Microscope System Overview





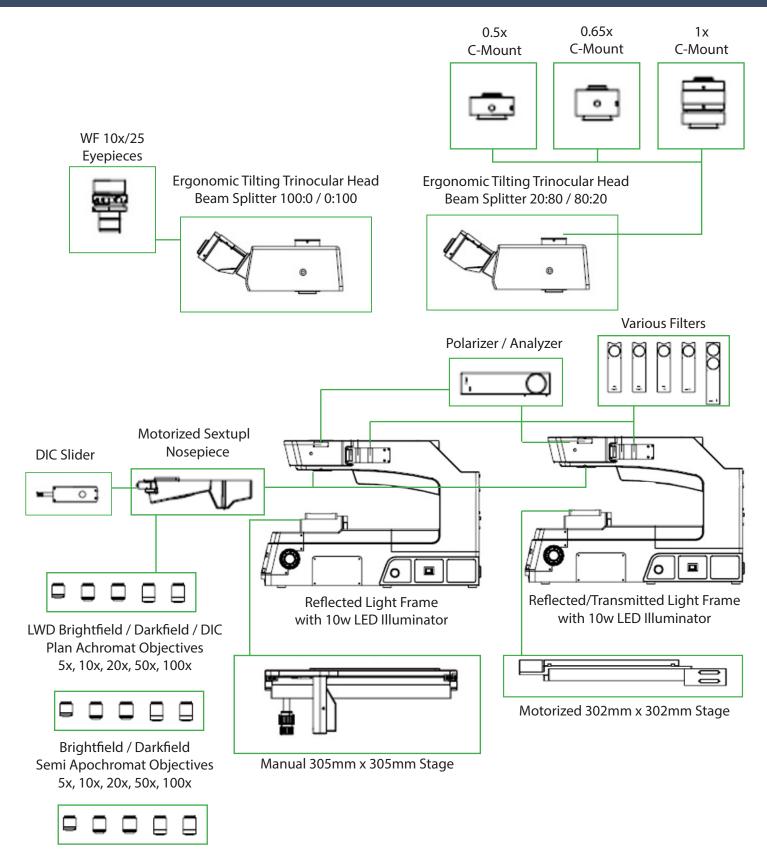
LWD Brightfield / Darkfield Semi Apochromat Objectives 5x, 10x, 20x, 50x, 100x

info@feinoptic.com

www.feinoptic.com



## Fein Optic M50-12 Advanced Semicondcutor Microscope System Overview



LWD Brightfield / Darkfield Semi Apochromat Objectives 5x, 10x, 20x, 50x, 100x



info@feinoptic.com www.feinoptic.com